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Invention:

COMPOSITION FOR ANTIREFLECTIVE COATING AND METHOD FOR FORMING SAME

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(21)Application number : 07-131096 (71)Applicant : HOECHST IND KK

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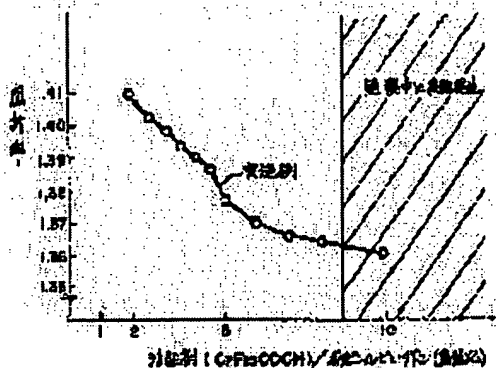
YOSHIDA TAKEO

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(54) COMPOSITION FOR ANTIREFLECTION COATING

(57)Abstract:

PURPOSE: To obtain a compsn. for forming a high quality anti-interference film on a photoresist film by incorporating perfluoro alkylcarboxylic acid, org. amine, polyvinylpyrrolidone and water.

CONSTITUTION: This compsn. contains perfluoroalkylcarboxylic acid, org. amine, polyvinylpyrrolidone and water. The perfluoroalkylcarboxylic acid is a compd. represented by the formula  $C_nF_{2n+1}COOH$  [where (n) is 5-10] and  $C_7F_{15}COOH$  is preferably used. The perfluoroalkylcarboxylic acid is used as an activator and dissolves under coexistence of a basic substance. The basic substance used here is the org. amine and alkanolamine, especially monoethanolamine is preferably used. By the combination of the components, a lower refractive index is ensured and a slightly soluble layer is not formed on a resist.



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